

AMENDMENT

In the claims:

Please amend claims 1, 7, 13, and 19 as follows:

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1. (Twice Amended) A device for generating a plurality of electron beams comprising:

- a source of radiation;
- a spatial light modulator having a position so as to modulate said radiation emanating from said source of radiation; and
- a photocathode having a position so as to receive said modulated radiation wherein said photocathode simultaneously produces a plurality of electron beams under impact by said modulated radiation as result of said modulation of the radiation by the spatial light modulator.

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7. (Twice Amended) An electron beam lithography system comprising:

- a source of radiation;
- a spatial light modulator having a position so as to modulate said radiation emanating from said source of radiation;
- a photocathode having a position so as to receive said modulated radiation wherein said photocathode simultaneously produces a plurality of electron beams under impact by said modulated radiation as result of said modulation of the radiation by the spatial light modulator; and
- an electron beam optical column having a position so as to receive said plurality of electron beams and to direct said plurality of electron beams onto a target.

13. (Twice Amended) A method of producing a plurality of electron beams comprising:

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- a) directing radiation onto a spatial light modulator, thereby modulating said radiation; and
- b) directing said modulated radiation onto a photocathode thereby simultaneously producing a plurality of electron beams as result of said modulation of the radiation by the spatial light modulator.

19. (Twice Amended) A method of performing lithography with multiple breams of electrons comprising:

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- a) directing radiation onto a spatial light modulator, thereby modulating said radiation;
- b) directing said modulated radiation onto a photocathode thereby simultaneously producing a plurality of electron beams as result of said modulation of the radiation by the spatial light modulator; and
- c) directing said plurality of electron beams onto an acceptance region of an electron beam optical column, producing thereby a plurality of electron beams impacting a target located at the target end of said electron beam optical column.